

What Is Claimed Is:

1. A method, comprising the steps of:

(a) searching for a defect on a photomask with a mask marking inspection system, the mask marking inspection system including a photomask inspection apparatus and a mark installer linked with the photomask inspection apparatus; and

(b) disposing a defect finder mark on the photomask with the mark installer.

2. The method according to claim 1 wherein the step of searching for a defect on a photomask includes the step of locating a defect on the photomask.

3. The method according to claim 1 wherein the step of searching for a defect includes the step of searching for the defect about a dense pattern array of the photomask.

4. The method according to claim 1 wherein the step of searching for a defect includes the step of searching for an elusive defect.

5. The method according to claim 1 wherein the step of disposing a defect finder mark on the photomask includes the step of establishing a location of the defect finder mark that is adjacent to the defect.

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6. The method according to claim 1 wherein the step of disposing a defect finder mark on the photomask includes the step of establishing a size for the defect finder mark so that the defect finder mark is detected with a mask repair device.

7. The method according to claim 1 further comprising the step of searching for the defect finder mark on the photomask with the mask repair device.

8. The method according to claim 1 further comprising the step of repairing the defect with the mask repair device.

9. The method according to claim 1 further comprising the step of eliminating the defect finder mark from the photomask.

10. The method according to claim 9 wherein the step of eliminating the defect includes depositing a filling agent on the defect finder mark.

11. The method according to claim 9 further including the step of forming a photoresist image on a wafer substrate with the photomask.

12. A back-end method for photomask making, comprising the steps of:

(a) inspecting a photomask, inspecting including the steps of searching for a defect on the photomask with a mask marking inspection system, the mask marking inspection system including a photomask inspection apparatus and a mark installer linked with the photomask inspection apparatus, and disposing a defect finder mark on the photomask with the mark installer; and

(b) repairing the defect on the photomask.

13. The back-end method according to claim 12 further comprising the step of cleaning the photomask.

14. The back-end method according to claim 12 further comprising the step of applying pellicle to the photomask.

15. The back-end method according to claim 12 wherein the step of searching for a defect includes the step of searching for the defect about a dense pattern array of the photomask.

16. The back-end method according to claim 12 wherein the step of searching for a defect includes the step of searching for an elusive defect.

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17. The back-end method according to claim 12 wherein the step of disposing a defect finder mark on the photomask includes the step of establishing a location of the defect finder mark that is adjacent to the defect.

18. The back-end method according to claim 12 wherein the step of disposing a defect finder mark on the photomask includes the step of establishing a size for the defect finder mark so that the defect finder mark is detected with a mask repair device.

19. The back-end method according to claim 12 further comprising the step of searching for the defect finder mark on the photomask with the mask repair device.

20. The back-end method according to claim 12 further comprising the step of eliminating the defect finder mark from the photomask.